This listing of claims will replace all prior versions, and listings, of claims in the application:

**Listing of Claims:** 

1. (Withdrawn) A method for manufacturing an organic electroluminescence device, comprising:

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a first film-forming step for sequentially forming an anode layer and an organic layer

including a light-emitting layer on a substrate; and

a second film-forming step for forming an alkali metal or a compound thereof as the

cathode layer and then depositing a low electric resistance metal, wherein

in the second film-forming step, the alkali metal or compound thereof is diffused in the

low electric resistance metal and the organic layer.

2. (Withdrawn) The method for manufacturing an organic electroluminescence device according

to claim 1, wherein the alkali metal or compound thereof is comprised of Cs or a compound

thereof.

3. (Withdrawn) The method for manufacturing an organic electroluminescence device according

to claim 2, wherein the compound is comprised of one of oxides, nitrides, fluorides, sulfides, and

mixtures of the same.

4. (Withdrawn) The method for manufacturing an organic electroluminescence device according

to claim 2, wherein in the second film-forming step, a film thickness sensor in which an organic

film is previously formed on a quartz crystal is set at a position different from a position of the

4

Application No. 10/827,330 Attorney Docket No. 26102

Response to Office Action of July 31, 2006

substrate, and the Cs is simultaneously formed on the organic layer and the organic film, whereby a thickness of the Cs deposited on the organic layer is measured in real-time through the film thickness sensor.

- 5. (Withdrawn) The method for manufacturing an organic electroluminescence device according to claim 4, wherein in the second film-forming step, a deposition rate of the alkali metal or compound thereof is a value in a range from 0.05 nm/sec to 0.1 nm/sec.
- 6. (Withdrawn) The method for manufacturing an organic electroluminescence device according to claim 4, wherein in the second film-forming step, a deposition rate of the low electric resistance metal is a value in a range from 1 nm/sec to 10 nm/sec.
- 7. (Currently Amended) An organic electroluminescence device comprising:

an anode layer formed on a substrate;

an organic layer which is formed on the anode layer and includes a light-emitting layer;

and

a cathode layer <u>having</u>:

an alkali metal compound layer which is made of an alkali metal compound including Cs and oxygen and is formed directly on the organic light-emitting layer; and

<u>a low electric resistance metal layer</u> in which an alkali metal or a compound thereof

<u>which</u> is <u>diffused in made of</u> a low electric resistance metal <u>and is formed directly on the alkali</u>

<u>metal compound layer</u>, wherein

Application No. 10/827,330 Attorney Docket No. 26102 Response to Office Action of July 31, 2006

an ion radius of the alkali metal among the alkali metals and compounds thereof is larger

than that of the low electric resistance metal both of the light-emitting layer and the low electric

resistance metal layer enable the Cs to be diffused.

8. - 9. (Cancelled)

10. (Original) The organic electroluminescence device according to claim 8, wherein the Cs

forms a layer having a thickness in a range from 10 to 20 nm in the cathode layer.

11. (Original) The organic electroluminescence device according to claim 8, wherein the low

electric resistance metal forms a layer having a thickness of substantially 200 nm in the cathode

layer.

6